## INFORMATION DISCLOSURE CITATION

Atty. Docket No.	3180.0350	LA F JOS	Appln. No.	10/760,522	
Applicant	Nakamura et ai.	2 200	·		
Filing Date	January 21, 2004	Mile Se	Group:	Unknown	

		U.S. PATEN	T DOCUMENTS			
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
DC	5,889,686	3/30/99	Mimotogi et al.			
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	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
DC	2000-29217	1/28/00	Japan	1	1	Abstract
DC	4-44312	2/14/92	Japan			Abstract
DC	1-188859	7/28/89	Japan	۰		Abstract

	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
DC	Nakamura et al., "Influence of Alkaline Concentration Variation on CD in KrF Resist Development," Journal of Photopolymer Science and Technology (4/20/01), pp. 435-438
	Nakamura et al., "Impact of Development Reaction Products on GD in View of Developer Alkaline Concentration Deviation," SPIE (2001), p. 729

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B/08: Substitute for form	1449A/HTO	2000	C	omplete if Known	
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Initials	No.1	Number-Kind Code <sup>2</sup> (d kno:m)	Publication Date MM-DD-YYYY	Applicant of Cited Document	Relevant Passages or Relevant Figures Appear
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Note: Copies of the U.S. Patent Documents are not Required in IDS filed after October 21, 2004

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Examiner Signature	/Dwin Craig/ (11/22/2006)	Date Considered	

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